

Form PTO 1449 (Modified)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO. 293482US0PCT		SERIAL NO. 10/588,080	
LIST OF REFERENCES CITED BY APPLICANT				APPLICANT Naoyoshi HATAKEYAMA, et al.			
				FILING DATE January 10, 2007		GROUP 1762 1621	
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
	AM						
	AN						
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO		
/YV/	AO	WO 03/104182 A1	12/18/2003	WIPO			
/YV/	AP	EP 0 999 474 A1	5/10/2000	Europe			
/YV/	AO	EP 1 577 285 A1	9/21/2005	Europe			
/YV/	AK	EP 1 803 708 A1	7/4/2007	Europe			
	AS						
	AT						
	AU						
	AV						
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)							
/YV/	AW	K. E. GONSALVES, et al., "High performance resist for EUV lithography", DATABASE CA [ONLINE], CHEMICAL ABSTRACTS SERVICE, XP-002461455, accession no. 2004: 1001937, Microelectronic engineering, 2005, 1 Page					
	AX						
	AY						
	AZ						
					<input type="checkbox"/> Additional References sheet(s) attached		
Examiner		/Yevgeny Valenrod/			Date Considered 03/23/2009		

*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.